

BS EN 62047-16:2015



BSI Standards Publication

Semiconductor devices — Micro-electromechanical devices

Part 16: Test methods for determining
residual stresses of MEMS films — Wafer
curvature and cantilever beam deflection
methods

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National foreword

This British Standard is the UK implementation of EN 62047-16:2015. It is identical to IEC 62047-16:2015.

The UK participation in its preparation was entrusted to Technical Committee EPL/47, Semiconductors.

A list of organizations represented on this committee can be obtained on request to its secretary.

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Amendments/corrigenda issued since publication

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